b) Amendments to the Specification

Please substitute the paragraph beginning at page 43, line 7 and ending at page 44, line 18 with the following replacement paragraph which is marked-up to show changes via strikethrough or underlining:

--Particularly, as shown in Fig. 1, in the inside of the film-forming vessel 101, the conductive substrate 102 is held on a substrate holder 103, and the conductive substrate 102 is electrically earthed together with the film-forming vessel 101. Reference numeral 104 indicates a heater 104 which is provided in the substrate holder 103. The substrate 102 can be heated to and maintained at a prescribed temperature by means of the heater 104 upon film formation. The discharge electrode 105 is provided at a position to oppose the substrate 102 in the film-forming vessel 101. ~~Reference numeral 106 indicates a cathode electrode which is provided at the discharge electrode 105~~. Reference numeral 107 indicates a high frequency power source which is connected to the discharge electrode 105 through a matching circuit 108 and a block condenser 109. Reference numeral 119 indicates a high frequency signal generator which is connected to the high frequency power source 107. Reference numeral 111 indicates a power amplifier [comprising a high speed power amplifier 4055 (produced by NF CIRCUIT DESIGN BLOCK Company)] which is connected to the auxiliary electrode 110. Reference numeral 112 indicates a high frequency signal generator [comprising a multifunction synthesizer wave ~~factry~~ factory 1952 (produced by NF CIRCUIT DESIGN BLOCK Company)] which is connected to the power amplifier 111. Reference numeral 113 indicates an oscilloscope which is connected

to the auxiliary electrode 110. The oscilloscope 113 is used for measuring a surface potential of the auxiliary electrode 110. The film-forming vessel 101 is provided with a raw material gas introduction pipe 115 which is extending from a raw material gas supply system 114 comprising a plurality of reservoirs each containing a desired raw material gas therein. The film-forming vessel 101 is also provided with an exhaust pipe 117 which is connected to an exhaustion device 116 comprising a vacuum pump. Reference numeral 118 indicates a throttle valve which is provided at the exhaust pipe 117.

Please substitute the paragraph beginning at page 47, line 17 and ending at page 49, line 3, with the following replacement paragraph marked-up to show changes therein.

--Particularly, as shown in Fig. 14, the film-forming vessel 101 is electrically earthed. A heater 104 is provided in the substrate holder 103 so that the substrate 102 held on the substrate holder 103 can be heated to and maintained at a prescribed temperature by means of the heater 104 upon film formation. The auxiliary electrode 110 is arranged between the heater 104 and the substrate 102. Reference numeral 105 indicates a discharge electrode shaped in a plate form which is provided at a position to oppose the substrate 102 in the film-forming chamber 101. ~~Reference numeral 106 indicates a cathode electrode which is provided at the discharge electrode 105~~. Reference numeral 107 indicates a high frequency power source which is connected to the discharge electrode 105 through a matching circuit 108 and a block condenser 109. Reference

numeral 119 indicates a high frequency signal generator which is connected to the high frequency power source 107. Reference numeral 111 indicates a power amplifier [comprising a high speed power amplifier 4055 (produced by NF CIRCUIT DESIGN BLOCK Company)] which is connected to the auxiliary electrode 110. Reference numeral 112 indicates a high frequency signal generator [comprising a multifunction synthesizer wave ~~factory~~ factory 1952 (produced by NF CIRCUIT DESIGN BLOCK Company)] which is connected to the power amplifier 111. Reference numeral 113 indicates an oscilloscope which is connected to the auxiliary electrode 110. The oscilloscope 113 is used for measuring a surface potential of the auxiliary electrode 110. The film-forming vessel 101 is provided with a raw material gas introduction pipe 115 which is extending from a raw material gas supply system 114 comprising a plurality of reservoirs each containing a desired raw material gas therein. The film-forming vessel 101 is also provided with an exhaust pipe 117 which is connected to an exhaustion device 116 comprising a vacuum pump. Reference numeral 118 indicates a throttle valve which is provided at the exhaust pipe 117.--

Please replace the Abstract of the Disclosure at page 94 with a substitute Abstract marked-up to show changes.